

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	29	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) with (clean\$3 or postclean\$3) with (season\$3))	US-PGPUB; USPAT	OR	ON	2006/01/11 12:56
L4	41	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) with (clean\$3 or postclean\$3) with ((coat\$3 or deposit\$3 or passivat\$4) near3 (showerhead or wall or (shower adj head) or (gas adj distribution adj plate))))	US-PGPUB; USPAT	OR	ON	2006/01/11 12:57
L6	32	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel or showerhead or (shower adj head) or (gas adj distribut\$4 adj plate)) same (clean\$3 or postclean\$3 or dryclean\$3 or preclean\$3) same (season\$3))	US-PGPUB; USPAT	OR	ON	2006/01/11 12:58
L7	5	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel or showerhead or (shower adj head) or (gas adj distribut\$4 adj plate)) same (clean\$3 or postclean\$3 or dryclean\$3 or preclean\$3) same (season\$3))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 12:59
L8	7	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) with (clean\$3 or postclean\$3) with ((coat\$3 or deposit\$3 or passivat\$4) near3 (showerhead or wall or (shower adj head) or (gas adj distribution adj plate))))	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:00
L9	31	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) with (clean\$3 or postclean\$3)) and ((chamber or reactor or vessel or showerhead or (shower adj head) or (gas adj distribut\$4 adj plate)) with (season\$3))	US-PGPUB; USPAT	OR	ON	2006/01/11 13:00
L10	11	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) same season\$4 same (temperature) same pressure same (thick\$4 or time))	US-PGPUB; USPAT	OR	ON	2006/01/11 13:02

L11	13	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) same season\$4 same (temperature) same pressure)	US-PGPUB; USPAT	OR	ON	2006/01/11 13:03
L12	2	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) same season\$4 same (temperature) same pressure)	EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:06
L13	12	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) same season\$4 same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:11
L14	12	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel) same season\$4 same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:49
L15	3	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel or vessell) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) with (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer) same season\$4 same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:17

L16	58	(Li.in. or Lu.in. or (taiwan adj semiconductor).as.) and ((chamber or reactor or vessel or vessel) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) with (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer) same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:19
L17	55	16 not (15 or 14)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:19
L18	317	(438/905).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:28
L19	457	(427/534).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L20	531	(427/237).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L21	897	(427/239).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L22	279	(427/249.15).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L23	694	(427/255.28).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L24	387	(427/255.37).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L25	411	(427/255.394).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43
L26	1786	(134/1.1,1.2,22.1).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:43

L27	4628	L19 L20 L21 L22 L23 L24 L25 L26	US-PGPUB; USPAT	OR	ON	2006/01/11 13:43
L28	3	(L20 or L21) and L22	US-PGPUB; USPAT	OR	ON	2006/01/11 13:43
L29	12	(L20 or L21) and L24	US-PGPUB; USPAT	OR	ON	2006/01/11 13:43
L30	7	(L20 or L21) and L25	US-PGPUB; USPAT	OR	ON	2006/01/11 13:44
L31	10	(L20 or L21) and L26	US-PGPUB; USPAT	OR	ON	2006/01/11 13:45
L32	317	(438/905).CCLS.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/01/11 13:46
L33	3	(L20 or L21) and L32	US-PGPUB; USPAT	OR	ON	2006/01/11 13:46
L34	8	(L19) and L32	US-PGPUB; USPAT	OR	ON	2006/01/11 13:46
L35	0	L22 and L32	US-PGPUB; USPAT	OR	ON	2006/01/11 13:46
L36	3	L24 and L32	US-PGPUB; USPAT	OR	ON	2006/01/11 13:46
L37	0	L25 and L32	US-PGPUB; USPAT	OR	ON	2006/01/11 13:46
L38	31	L19 and L26	US-PGPUB; USPAT	OR	ON	2006/01/11 13:47
L39	4628	L19 L20 L21 L22 L23 L24 L25 L26	US-PGPUB; USPAT	OR	ON	2006/01/11 13:47
L40	65	L39 and ((chamber or reactor or vessel or showerhead or (shower adj head) or (gas adj distribut\$4 adj plate) or manifold) same (clean\$3 or postclean\$3 or dryclean\$3 or preclean\$3) same (season\$3))	US-PGPUB; USPAT	OR	ON	2006/01/11 13:47
L43	18	39 and ((chamber or reactor or vessel) same season\$4 same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:59

L44	98	((chamber or reactor or vessel) same season\$4 same (SiH4 or "SiH.sub.4" or silane or monosilane or \$10silane or DCS or TMS or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2" or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:11
L45	80	44 not 43	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 13:59
L46	11	((chamber or reactor or vessel) same season\$4 same (dichlorosilane or (di adj chloro adj silane) or (di adj chlorosilane) or (dichloro adj silane) or DCS or (silicon adj dichloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:15
L47	135	(season\$4 same (dichlorosilane or (di adj chloro adj silane) or (di adj chlorosilane) or (dichloro adj silane) or DCS or (silicon adj dichloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:14
L48	124	47 not 46	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:14
L49	11	((chamber or reactor or vessel) same season\$4 same (\$4chlorosilane or (di adj chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or DCS or (silicon adj \$4chloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:16

L50	11	((chamber or reactor or vessel) same season\$4 same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or DCS or (silicon adj \$4chloride) or SiCl ₂ H ₂ or SiH ₂ Cl ₂ or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:50
L51	1117	((chamber or reactor or vessel or vessell) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) with (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or DCS or (silicon adj \$4chloride) or SiCl ₂ H ₂ or SiH ₂ Cl ₂ or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:19
L52	487	((chamber or reactor or vessel or vessell) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) near3 (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or DCS or (silicon adj \$4chloride) or SiCl ₂ H ₂ or SiH ₂ Cl ₂ or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:18
L53	48	51 and 39	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:19

L54	277	((chamber or reactor or vessel or vessel)) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) with (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or (silicon adj \$4chloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:57
L55	662	(plasma or HDP or PECvd or PACvd) same (\$4cvd or coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or (silicon adj \$4chloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2") same (ammonia or NH3 or "NH.sub.3") same ((silicon adj nitride) or SiN or Si3N4 or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:44
L56	17	(HDP) same (\$4cvd or coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$4chlorosilane or (chloro adj silane) or (di adj chlorosilane) or (\$4chloro adj silane) or (silicon adj \$4chloride) or SiCl2H2 or SiH2Cl2 or "SiCl.sub.2H.sub.2" or "SiCl.sub.2 H.sub.2" or "SiH.sub.2Cl.sub.2" or "SiH.sub.2 Cl.sub.2") same (ammonia or NH3 or "NH.sub.3") same ((silicon adj nitride) or SiN or Si3N4 or "Si.sub.3N.sub.4" or "Si.sub.3 N.sub.4"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:44
L57	4	((chamber or reactor or vessel) same season\$4 same (\$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:56

L58	11	((chamber or reactor or vessel) same season\$4 same (TMS or \$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:52
L59	27	((chamber or reactor or vessel) same season\$4) and (\$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 15:13
L60	23	59 not 57	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:53
L61	4	(season\$4 same (\$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:56
L62	40	((chamber or reactor or vessel or vessel) with (wall or showerhead or (shower adj head) or inside or interior or inner or (gas adj distribution adj plate)) with (coat\$5 or deposit\$5 or season\$5 or passivat\$5 or film or layer or precoat\$5) same (\$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 14:58
L63	0	(season\$4) and ((\$5methylsilane or (\$5methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]")) same (plasma or \$4cvd or HDP or (vapor adj deposit\$5)) same (CO2 or "CO.sub.2" or (carbon adj dioxide)) same (SiC or (silicon adj carbide)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 15:16

L64	27	(((\$methylsilane or (\$methyl adj silane) or "Si(CH.sub.3).sub.3H" or "SiCH3.sub.3H" or "Si(CH.sub.3).sub.3 H" or "[Si(CH.sub.3).sub.3H]") same (plasma or \$4cvd or HDP or (vapor adj deposit\$5)) same (CO2 or "CO.sub.2" or (carbon adj dioxide)) same (SiC or (silicon adj carbide)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/11 15:22
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